



00684.003542.

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

YASUHISA INAO, ET AL.

Application No.: 10/663,691

Filed: September 17, 2003

For: MASK, EXPOSURE  
APPARATUS, AND  
EXPOSURE METHOD

December 18, 2003

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

In compliance with the duty of disclosure under 37 C.F.R. § 1.56 and in accordance with the practice under 37 C.F.R. §§ 1.97 and 1.98, the Examiner's attention is directed to the documents listed below and on the enclosed Form PTO-1449. Copies of documents (2) and (3) are also enclosed, along with an English-language abstract for document (2).

- (1) U.S. Patent No. 6,171,739
- (2) Japan 2000-112116
- (3) "Sub-diffraction-limited patterning using evanescent near-field optical lithography," M.M. Alkaisi et al., Applied Physics Letters (1999), Vol. 75, No. 22, pp. 3560-3562.

These documents were cited on page 8 of the subject application, and might be deemed relevant for the reasons noted therein.

A copy of the newly cited U.S. Patent Application is not being provided in accordance to the Pre-Official Gazette Notice dated, July 11, 2003, entitled "Information Disclosure Statements Filed Without Copies Of U.S. Patents and Published Applications in Patent Applications filed after June 30, 2003.

Inasmuch as the subject application has not yet received a first Office Action, it is believed that this Information Disclosure Statement is timely. See 37 C.F.R. 1.97(b)(3). Accordingly, the Examiner is urged to study this information in its entirety and to form an independent determination of the materiality of the information to the claimed invention. Additionally, the Examiner is requested to indicate that this information has been considered by initialing the appropriate portion of the Form PTO-1449.

Applicants' undersigned attorney may be reached in our Costa Mesa, California office by telephone at (714) 540-8700. All correspondence should continue to be directed to our address given below.

Respectfully submitted,



\_\_\_\_\_  
Attorney for Applicants  
Registration No. 54,336

FITZPATRICK, CELLA, HARPER & SCINTO  
30 Rockefeller Plaza  
New York, New York 10112-3800  
Facsimile: (212) 218-2200

ATTY DOCKET NO. 00684.003542.

APPLICATION NO. 10/663,691

APPLICANT YASUHISA INAO, ET AL.

FILING DATE September 17, 2003

GROUP N/Y/A

M P E  
J C 139  
DEC 19 2003  
PATENT & TRADEMARK OFFICE

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
	6,171,739	01/09/01	Spence et al.	430	30	

## FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES/NO/ OR ABSTRACT
	2000-112116	04/21/00	Japan			Abstract

## OTHER DOCUMENT(S) (Including Author, Title, Date, Pertinent Pages, Etc.)

	"Sub-diffraction-limited patterning using evanescent near-field optical lithography," M.M. Alkaisi et al., Applied Physics Letters (1999), Vol. 75, No. 22, pp. 3560-3562.

EXAMINER

DATE CONSIDERED

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

Sheet 1 of 1